

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of	:	Customer Number: 20277
	:	
Toshihiko TANAKA	:	Confirmation Number: 3832
	:	
Application No.: 10/551,553	:	Group Art Unit: 2812
	:	
Filed: October 03, 2005	:	Examiner: JELSMA, Jonathan G.
	:	
For: PROCESS FOR FABRICATING SEMICONDUCTOR DEVICE AND METHOD FOR GENERATING MASK PATTERN DATA	:	

**AMENDMENT**

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the non-final Office Action dated September 17, 2008 having a three-month shortened statutory period for response set to expire December 17, 2008, please amend the above-identified application as follows:

**Amendments to the Specification** begin on page 2 of this paper.

**Amendments to the Claims** are reflected in the listing of claims beginning on page 3 of this paper. This listing of claims replaces all prior versions, and listings, of claims in the application.

**Remarks** begin on page 4 of this paper.